



Beam Initiative

THE FINE LINE : VIDEOS FOR THE EBEAM COMMUNITY
WINTER 2013

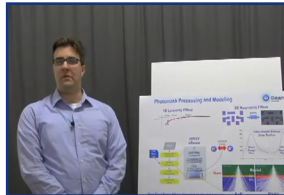
SHOT TALK - A WORD FROM OUR SPONSOR

Aki Fujimura, CEO of D2S, discusses the need for greater investments in simulation-based eBeam technology to support the continuation of Moore's Law.



FROM THE WHITE BOARD

Ryan Pearman of D2S explains why shapes taped out are not the shapes on the mask in the first part of a series on Photomask Processing and Modeling.



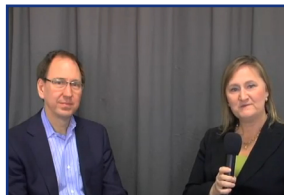
TECH TALK

Samsung and D2S evaluate a new measure of mask quality (eMEEF) for sub-100-nm and curved mask shapes.

$$eMEEF = N \frac{\Delta CD_{wafer}}{\Delta eBeamDose}$$

PERSPECTIVES

Hugh Durdan of Xilinx offers a fabless manufacturer's perspective on the implications of rising mask complexity and costs.



VIDEO ARCHIVE

BACUS 2012



Sergey Babin: Bacus 2012



Brian Grenon: Bacus 2012



Aki Fujimura: Bacus 2012

SPIE 2012



Ryan Pearman: SPIE 2012



David Lam: SPIE 2012



Mike Smayling: SPIE 2012

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The eBeam Initiative is a forum dedicated to the education and promotion of new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please e-mail requests@ebeam.org or visit www.ebeam.org